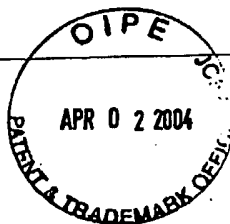


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**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: BASELMANS et al.	
Appln. No.: 09/905,198	
Filing Date: July 16, 2001	
Examiner: Mohamedulla	Group Art Unit: 3046

Date: April 2, 2004

Page 1 of 1

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

SRM	AR	Peter D. Buck et al., "Phase Shift Mask Applications," Proceedings of SPIE – The International Society for Optical Engineering, Optical/Laser Microlithography IV, 6-8 March 1991, Coversheet + 9 pages.				
SRM	BR	Tsuneo Terasawa et al., "Improved resolution of an i-line stepper using a phase-shifting mask," J. Vac. Sci. Technol B., Vol. 8, No. 6 Nov/Dec 1990, pp. 1300-1308.				
SRM	CR	Yong Liu et al., "Computer Aided Phase Shift Mask Design with Reduced Complexity," Department of Electrical Engineering and Computer Sciences, University of California at Berkeley, CA 94720, SPIE Vol. 1927 Optical/Laser Microlithography VI (1993) pp. 477-493.				
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Date Considered: 6/19/04

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